

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicant	:	Washio et al.
Appl. No.	:	10/561,802
Filed	:	December 22, 2005
For	:	DEVELOPER COMPOSITION FOR RESISTS AND METHOD FOR FORMATION OF RESIST PATTERN
Examiner	:	Le, Hoa Van
Group Art Unit	:	1752

**RESPONSE TO FINAL OFFICE ACTION****Mail Stop AF**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

In response to the final Office Action mailed **January 30, 2007**, Applicants respectfully request consideration of the following remarks:

**The listing of claims** begins on page 2 of this paper. No amendments have been made. The claims are provided for the Examiner's convenience.

**Remarks/Arguments** begin on page 3 of this paper.